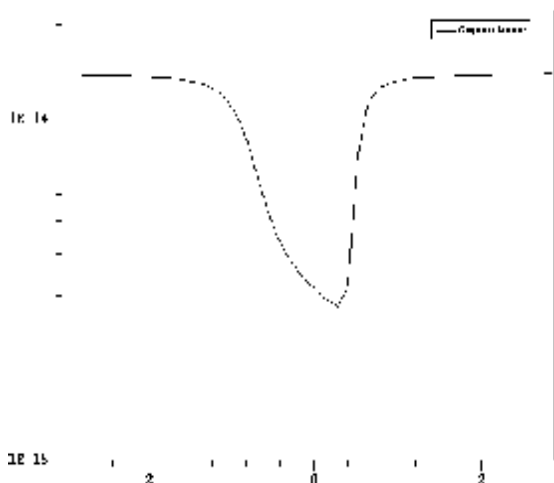


Home Work -3

Submitted By
Group3
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Q1a) The C-V char. Of MOS Capacitor are as shown in the following figures:



a) Low Freq.

Values obtained From INSPECT:

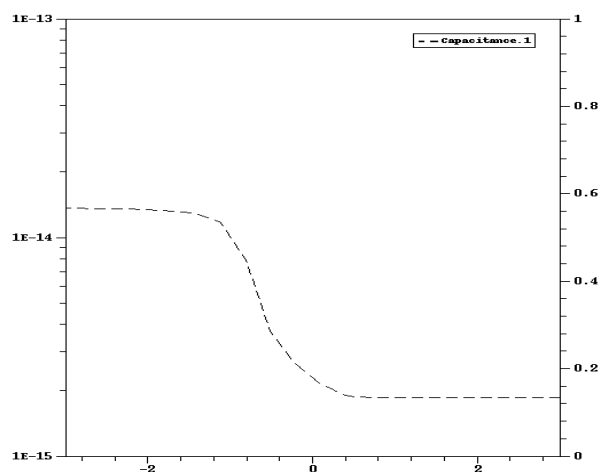
Vfb=-1.4v and Cfb=7.63fF.

Cox=13.34 fF

Theoretical values

Vfb=-0.96v(= ϕ_{ms}), Cfb=7.79 fF

Cmin=2.04/f(= $C_{ox} \cdot C_d / (C_{ox} + C_d)$), $C_d = \epsilon_s / W_d$



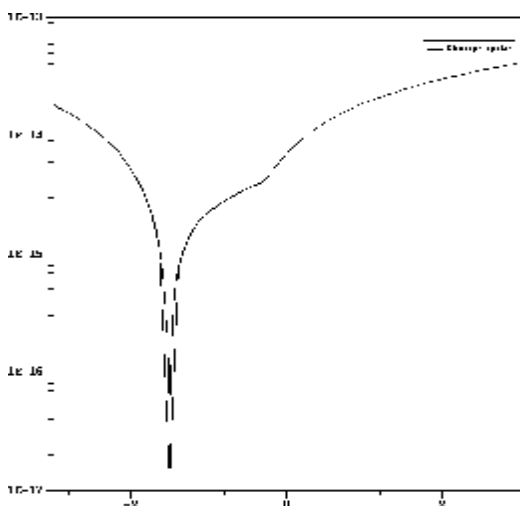
b) High Freq.

Cmin=1.83fF(for HFCV) and 2.29fF (for LFCV).

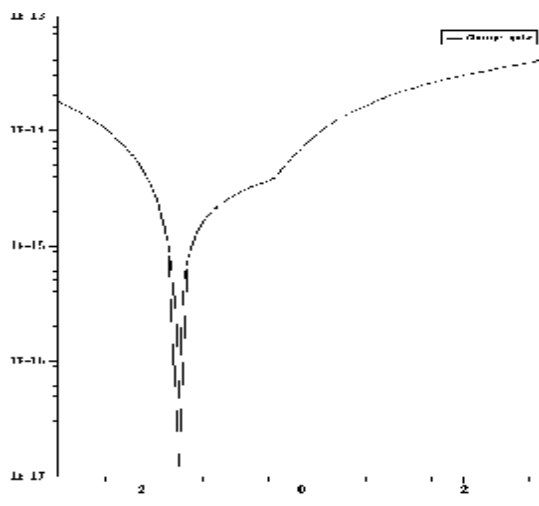
Vt= 0.384v.

$C_{ox} = \epsilon_{ox} \cdot A / T_{ox} = 13.81 \text{ fF}$

$V_t = \phi_{ms} + Q_d / C_{ox} + 2\phi_b = 0.214 \text{ V.}$

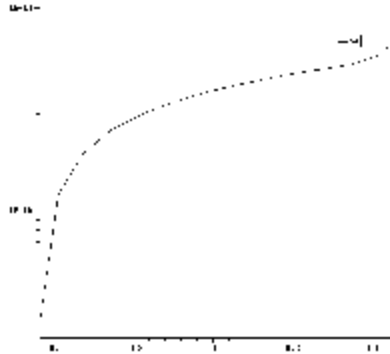


c) Low freq.



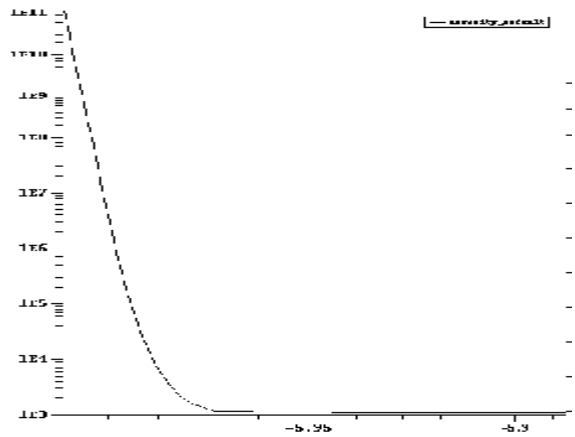
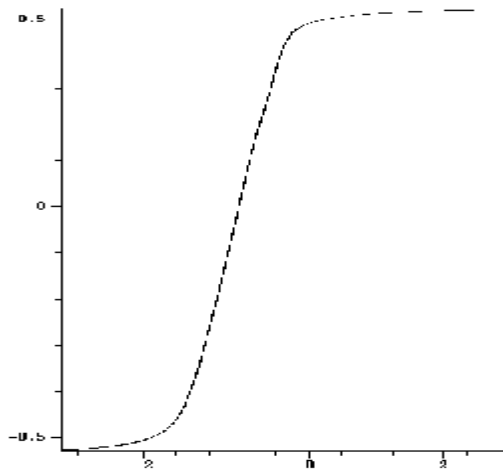
d) High freq.

The values from simulation for V_{fb} are different from that of theoretical values. While making the device we used Gatepoly as poly. Material and the barrier which it has defined is -0.55 v. even if we change this barrier we get the same plot so probably an offset is added to the ϕ_{ms} value.



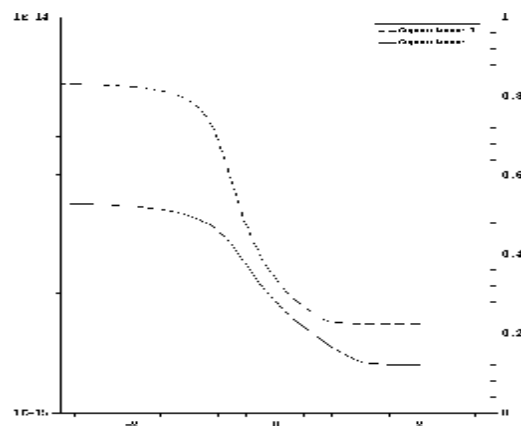
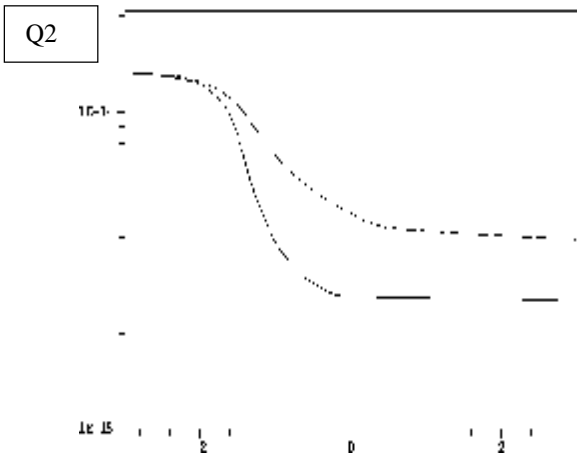
Variation of Depletion Width in MOS as a function of surface potential ϕ_s

b) Surface potential ψ_s vs. V_g :-the fig. Shows respective plot.



e) ψ_s vs. V_g

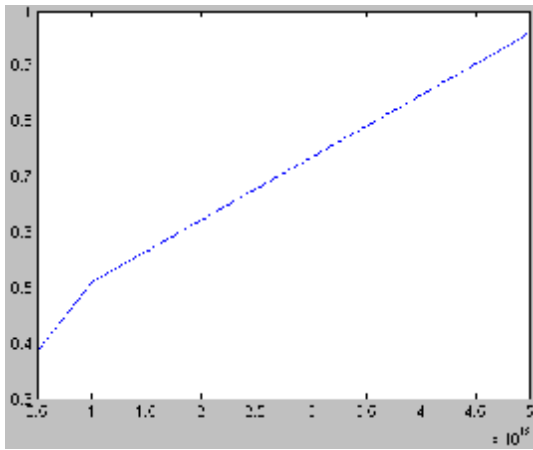
Q1) e Density Vs. X at $V_g = 3v$.



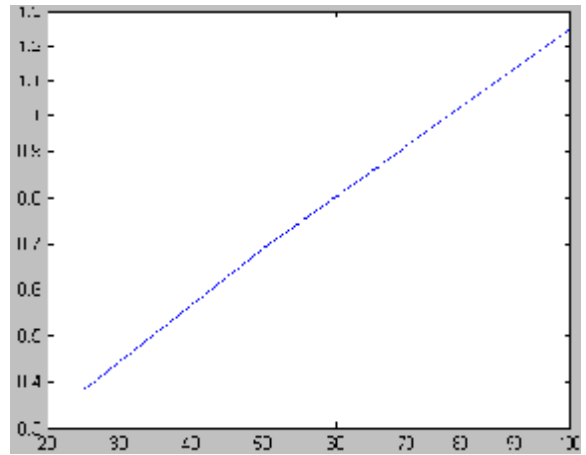
-----Cap. for $N_a=1e+18/cm^3$
Cap. for $N_a=5e+18/cm^3$

.....Cap. for $Tox=50 A$
 -----cap. for $Tox=100 A$

Q2)

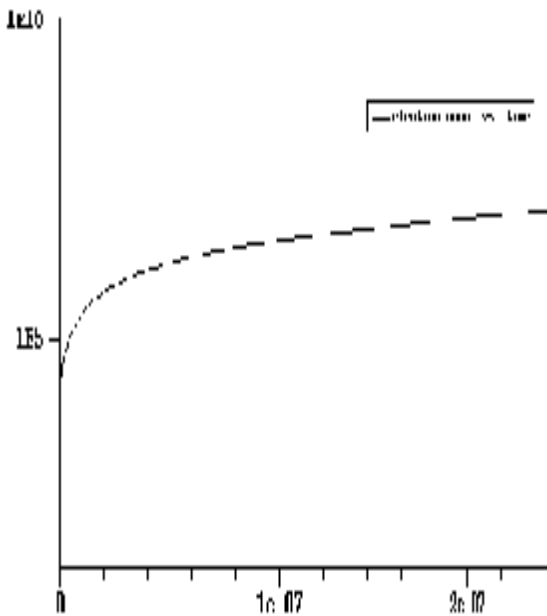


c) Fig. for V_t vs N_a



d) Fig. for V_t vs $Tox(A^0)$

Q3) The electron concentration as a function of time is plotted in the figure



Relation: The minority carrier resp. time is directly related to the recovery time and the electron and period of freq. At which LFCV char. are obtained in Q1 is of same order as that obtained in Q3. time period for 1 hz. Freq. Is 1 sec. And it is found that for response time $10e-8$ sec. Is observed at 0.96 sec.